

1 **IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

2 **PRIORITY** PATENT APPLICATION SERIAL NO. 08/696,243

3 **PRIORITY** FILING DATE 08/13/96

4 INVENTORSHIP Schuegraf

5 **PRIORITY** GROUP ART UNIT 2813

6 **PRIORITY** EXAMINER M. Whipple

7 ATTORNEY'S DOCKET NO. MI22-1098

8 TITLE Semiconductor Processing Methods of Chemical Vapor Depositing
9 SiO₂ on a Substrate

10 _____
11
12 Assistant Commissioner for Patents

13 Washington, D. C. 20231

14 Attention: Official Draftsman

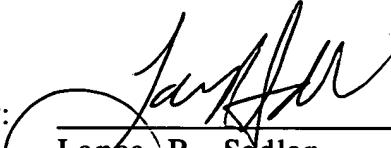
15
16 **SUBSTITUTE DRAWING REQUEST**

17 Please enter the enclosed substitute drawings in the
18 above-referenced application in place of drawings originally filed. The
19 content of the drawings are identical to those now on file in this
20 application.

1 Acknowledgment of receipt of the formal drawings and their
2 acceptance into the file is requested.

Respectfully submitted,

Date: 12/15/98

By: 

Lance R. Sadler

Reg. No.: 38,605

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Enclosures: 2 Formal Sheets of Drawings, Figs. 1-4